



First Call for Papers

2016 International Workshop on EUV and Soft X-Ray Sources

November 7-9, 2016, Amsterdam, The Netherlands

This leading annual workshop focuses on the latest scientific and technical developments related to extreme ultraviolet (EUV) and soft X-ray sources. In focus will be the generation of photons in this wavelength regime, using laser-produced plasma (LPP), discharge-produced plasma (DPP), high-harmonics generation (HHG), free electron lasers (FEL), synchrotrons and innovative concepts. We also welcome papers describing applications of these sources in EUV lithography for scanner and metrology applications, microscopy, and analytical instrumentation, and for supporting scientific research in material and biological sciences. Next to experimental studies, we encourage you to submit theoretical and modeling contributions.

Abstracts of 200 words or fewer should be sent to abstracts@euvlitho.com by August 15, 2016. Student papers are highly encouraged. Please, indicate whether an oral or poster presentation is preferred and include each author's full name, e-mail address, affiliation and mailing address. Please, also include a brief biography and photograph of the presenting author, for inclusion in the abstract book.

This workshop will be hosted by the Advanced Research Center for Nanolithography ([ARCNL](http://ARCNL.nl)), located in the Amsterdam Science Park ([ASP](http://ASP.nl)), in the city of Amsterdam, The Netherlands. The workshop will provide a forum for researchers and end-users in the EUV and soft X-ray areas to present their work and discuss a wide range of potential applications. The workshop proceedings will be published online and made available to all. Proceedings of the previous workshop are available online at www.euvlitho.com. This workshop is co-organized by EUV Litho, Inc. and ARCNL. For sponsorship opportunities, please contact Joost Frenken at frenken@arcnl.nl.

Abstracts

Submission Deadline
August 15, 2016

Submit to
abstracts@euvlitho.com

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Venue

Advanced Research Center
for Nanolithography, [ARCNL](http://ARCNL.nl)

Registration and Travel Info

Coming soon at
www.euvlitho.com

Organized by

